IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:
Application No.:

Varughese Mathew et al.

Group Art Unit:

1762

Date Filed:

10/650,002

Examiner:

Unassigned

Title:

August 27, 2003

SEMICONDUCTOR PROCESS AND COMPOSITION FOR FORMING A BARRIER

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Art Unit

Patricia Parks

INFORMATION DISCLOSURE STATEMENT (IDS)

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Serial No.

SIR:

In accordance with 37 C.F.R. §1.56 and in compliance with 37 C.F.R. §§1.97 and 1.98, the references listed on attached Form PTO/SB/08 and/or subsequently identified herein, are being submitted herewith for consideration by the United States Patent and Trademark Office. The Office has waived the requirement under 37 CFR 1.98 (a)(2)(i) for submitting a copy of each cited U.S. patent and each U.S. patent application publication for all U.S. national patent applications filed after June 30, 2003 and for all international applications that have entered the national stage under 35 USC § 371 after June 30, 2003. See 37 CFR 1.491(b).

l.	COPIES a.⊠ b.□	A legible copy of (i) each foreign patent(s); (ii) each publication or that portion which caused it to be listed; and (iii) all other information or that portion which caused it to be listed, is included herewith. Any patents, publications or other information which are listed on PTO/SB/08 which are not enclosed herewith were previously cited by or submitted to the PTO in one of the following applications which has been relied upon for an earlier filing date under 35 U.S.C. §120:		
		U.S. Serial Number	U.S. Filing Date	
II.	CONCISI a. ⊠ b. □ c. □	EXPLANATION OF THE RELEVANCE (check at least on Except as may be indicated below in (b) of this section, a are in the English language (concise explanation not requi A concise explanation of the relevance of all patents, public English language is as follows: The following additional information is provided for the Example 1.	all of the patents, publications or other information red). lications or other information listed that is not in the	
III. 🗌	The Exar	REFERENCE TO RELATED APPLICATION(S) niner is advised that the following co-pending application(sent application. By bringing this (these) applications to the confidentiality provisions of 35 U.S.C. §122.		

Filing Date

FEES

counterpart foreign application not more than three months prior to the filing of IDS; or no item of information contained in the IDS was cited in a communication from a foreign Patent Off counterpart foreign application, and to knowledge of the person signing the statement after reasonable inquiry, no item of information contained in the IDS was known to any individual designate C.F.R. 1.56(c) more than three months prior to the filing of this statement, or c. some of the items of information contained in the IDS were cited in a communication from a foreign Office. As to this information, the undersigned states that each item of information contained in the IDS cited in a communication from a foreign Patent Office in a counterpart foreign application not more that months prior to the filing of this IDS. As to the remaining information, the undersigned hereby states item of this remaining information contained in the IDS was cited in a communication from a foreign Office in a counterpart foreign application or, to the knowledge of the person signing the stateme making reasonable inquiry, no item of information contained in the IDS was known to any in designated in 37 C.F.R. 1.56(c) more than three months prior to the filing of this statement. VIII. PAYMENT OF FEES A check in the amount of is enclosed for the above-identified fee(s). Please charge Deposit Account No. 502117 in the amount of \$180.00 for the above-indicated fee(s).	IV. 🔯	THIS IDS a. □ b. □ c. ☑ d. □	within three months of the filing date of a national application other than a continued prosecution application under § 1.53(d) (37 C.F.R. §1.97(b)(1)). No fee or statement is required. within three months of the date of entry of the national stage as set forth in § 1.491 in an international application (37 C.F.R. §1.97(b)(2)). No fee or statement is required. before the mailing date of a first Office Action on the merits (37 C.F.R. §1.97(b)(3)). No fee or statement is required. before the mailing date of a first Office Action after the filing of a request for continued examination under § 1.114 (37 C.F.R. § 1.97(b)(4)). No fee or statement is required.
on or before payment of the issue fee and is accompanied by the following: 1) a statement under 37 C.F.R. §1.97(e) as provided below; and 2) charge Deposit Account 502117 the petition fee set forth in §1.17(p). VII. STATEMENT UNDER 37 C.F.R. §1.97(e) (check only one box, if applicable) The undersigned hereby states that a. each item of information contained in the IDS was cited in a communication from a foreign Patent Office counterpart foreign application not more than three months prior to the filing of IDS; or b. no item of information contained in the IDS was cited in a communication from a foreign Patent Office counterpart foreign application, and to knowledge of the person signing the statement after reasonable inquiry, no item of information contained in the IDS was known to any individual designate C.F.R. 1.56(c) more than three months prior to the filing of this statement, or c. some of the items of information contained in the IDS were cited in a communication from a foreign Office. As to this information, the undersigned states that each item of information contained in the ID cited in a communication from a foreign Patent Office in a counterpart foreign application not more the months prior to the filing of this IDS. As to the remaining information, the undersigned hereby states item of this remaining information contained in the IDS was cited in a communication from a foreign Office in a counterpart foreign application or, to the knowledge of the person signing the stateme making reasonable inquiry, no item of information contained in the IDS was known to any in designated in 37 C.F.R. 1.56(c) more than three months prior to the filing of this statement. VIII. PAYMENT OF FEES A check in the amount of is enclosed for the above-identified fee(s). Please charge Deposit Account No. 502117 in the amount of \$180.00 for the above-indicated fee(s). If Applicant has overlooked any additional fees, or if any overpayment has been made, the Commission hereby authorized to credit or debit Deposit Acc	V. 🔲	before th §1.311, o a. \square	ne mailing date of any of a Final Office Action under 37 C.F.R. §1.113, a Notice of Allowance under 37 C.F.R. or an action that otherwise closes prosecution in the application (See 37 C.F.R. §1.97(c)). No statement; therefore, charge Deposit Account 502117 the fee set forth in 37 C.F.R. §1.17(p).
The undersigned hereby states that a.	VI. 🗌	on or bef 1)	ore payment of the issue fee and is accompanied by the following: a statement under 37 C.F.R. §1.97(e) as provided below; and
A check in the amount of is enclosed for the above-identified fee(s). Please charge Deposit Account No. 502117 in the amount of \$180.00 for the above-indicated fee(s). If Applicant has overlooked any additional fees, or if any overpayment has been made, the Commission hereby authorized to credit or debit Deposit Account 502117.	VII.	The under a. b. b.	each item of information contained in the IDS was cited in a communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filling of IDS; or no item of information contained in the IDS was cited in a communication from a foreign Patent Office in a counterpart foreign application, and to knowledge of the person signing the statement after making reasonable inquiry, no item of information contained in the IDS was known to any individual designated in 37 C.F.R. 1.56(c) more than three months prior to the filling of this statement, or some of the items of information contained in the IDS were cited in a communication from a foreign Patent Office. As to this information, the undersigned states that each item of information contained in the IDS was cited in a communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filling of this IDS. As to the remaining information, the undersigned hereby states that no item of this remaining information contained in the IDS was cited in a communication from a foreign Patent Office in a counterpart foreign application or, to the knowledge of the person signing the statement after making reasonable inquiry, no item of information contained in the IDS was known to any individual
	VIII.		A check in the amount of is enclosed for the above-identified fee(s). Please charge Deposit Account No. 502117 in the amount of \$180.00 for the above-indicated fee(s). If Applicant has overlooked any additional fees, or if any overpayment has been made, the Commissioner is hereby authorized to credit or debit Deposit Account 502117 .

The above references are being cited only in the interests of candor and without any admission that they constitute statutory prior art or contain matter which anticipates the invention or which would render the same obvious, either singly or in a combination, to a person of ordinary skill in the art.

If the Examiner has any questions concerning this IDS, he/she is requested to contact the undersigned. If it is determined that this IDS has been filed under the wrong rule, the PTO is requested to consider this IDS under the proper rule (with a petition if necessary) and charge the appropriate fee to Deposit Account No. **502117**.

Respectfully submitted, Varughese Mathew et al.

MOTOROLA, INC. Customer Number 23125

Enclosures:

PTO/SB/08

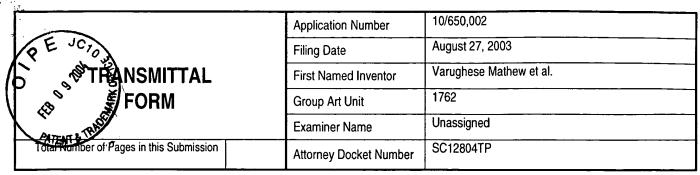
References
Foreign Search Report

Other:

SB/08

Reg. No. 42,038 Tel. 512.996.6839

Michael P. Noonan Attorney for Applicant(s)



ENCLOSURES (check all that apply)							
Fee Transmitta	al Form	Assignment Papers (for an Application)	After A	llowance			
Fee Att	ached	Drawing(s)	Appeal	nunication to Group Communication to Board eals and Interferences			
Amendment/R	eply	Licensing-Related papers	Appeal	Communication to Group Notice, Brief, Reply Brief)			
After Fi	nal	Petition		tary Information			
Affidav	ts/Declaration(s)	Petition to Convert to a Provisional Application	Status Letter with appropriate copies				
Extension of til	ne Request	Power of Attorney, Revocation, Change of Correspondence	L	Other Enclosure(s) (please identify below) Response to Restriction Requirement			
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PTO/SB/08A (04-03)

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

of

 Complete if Known

 Application Number
 10/650,002

 Filing Date
 August 27, 2003

 First Named Inventor
 Varughese Mathew et al.

 Group Art Unit
 1762

 Examiner Name
 Unassigned

 Attorney Docket Number
 SC12804TP

(use as many sheets as necessary)
Sheet

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. 1	Document Number Number -Kind Code² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	BA	6,528,409 B1	03/04/2003	Lopatin et al.	
	BB	2003/0111729 A1	06/19/2003	Leu et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. 1	Foreign Patent Document Country Code ³ Number ⁴ Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T 6

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No. 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Ţ2
	BC	Duch et al., "Development and Characterization of Co-Ni Alloys for Microsystems Applications," Journal of the Electrochemical Society, 2002, 149(4), pp. C201-C208.	
	BD	Homma et al., "Microstructural Study of Electroless-Plated CoNiP Ternary Alloy Films for Perpendicular Magnetic Recording Media," IEEE Transactions on Magnetics, November 1991, 27(6), pp. 4909-4911.	
	BE	Kohn et al., "Characterization of Electroless Deposited Co(W,P) Thin Films for Encapsulation of Copper Metallization," Materials Science and Engineering, 2001, A302, pp. 18-25.	
-	BF	Kohn et al., "Evaluation of Electroless Deposited Co(W,P) Thin Films as Diffusion Barriers for Copper Metallization," Microelectronic Engineering, 2001, 55, pp. 297-303.	
	BG	Petrov et al., "Electrochemical Study of the Electroless Deposition of Co(P) and Co (W,P) Alloys," Journal of the Electrochemical Society, 2002, 149(4), C187-C194.	
	ВН	Osaka et al., "Fabrication of Electroless NiReP Barrier Layer on SiO₂ without Sputtered Seed Layer," Electrochemical and Solid-State Letters, 2002, 5(1), pp. C7-C10.	
	BI	O'Sullivan et al., "Electrolessly Deposited Diffusion Barriers for Microelectronics," IBM Journal of Research and Development, September 1998, Vol. 42, No. 5, pp. 607-620.	
	BJ	Segawa et al., "Manufacturing-ready Selectivity of CoWP Capping on Damascene Copper Interconnects," Advanced Metallization Conference 2001, AMC 2001 Proceedings of the Conference, pp. 567-572.	
	BK	Shacham-Diamand et al., "Electroless Co(W,P) and Co (Mo,P) Deposition for Cu Metallization Applications," IEEE, 2001 6th International Conference on Solid State and Integrated Circuit Technology, Vol. 1, 2001, pp. 410-415.	
	BL	Shacham-Diamand <i>et al.</i> , "Electroless Deposition of Thin-Film Cobalt-Tungsten-Phosphorus Layers Using Tungsten Phosphoric Acid (H ₃ [P(W ₃ O ₁₀) ₄]) for ULSI and MEMS Application," <i>Journal of the Electrochemical Society</i> , 2001, 148(3), pp. C162-C167.	
	ВМ	Shacham-Diamand et al., "Material Properties of Electroless 100-200 nm Thick CoWP Films," Electrochemical Technology Applications in Electronics Proceedings of the Third International Symposium Electrochemical Society Proceedings, 2000, Vol. 99-34, pp. 102-110.	

Examiner	Date	
Signature	Considered	

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation, if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² See Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English Language Translation is attached.